



NOTES:

1. MATERIAL: UVFS
2. COATING (S1) : HIGH ENERGY LASER LINE COATING  
 $R_s, R_p > 99\% @ 780 \text{ nm}, 0^\circ - 45^\circ \text{ AOI}$
3. CLEAR APERTURE (S1) :  $> 90\%$  (CA)
4. SURFACE QUALITY (S1) : 20/10 (S/D)
5. SURFACE FLATNESS (S1) :  $\lambda / 10 @ 633 \text{ nm}$
6. PARALLELISM (S1, S2) :  $< 3 \text{ arcmin}$
7. CHAMFER:  $< 0.2 \text{ mm}, 45^\circ$
8. BACK SURFACE (S2) : FINE GROUND

|  |       |              |  |        |       |     |
|--|-------|--------------|--|--------|-------|-----|
| DRAWING PROJECTION                                     |       |              | <b>LBTEK</b>   |        |       |     |
|  | NAME  | DATE         | LPM20-780-HP   |        |       |     |
| DRAWN  | Lynne | JAN./12th/24 | HIGH ENERGY LASER LINE MIRROR<br>Ø 50.8 mm x 12 mm, 780 nm |        |       |     |
| APPROVAL   | CWZ   | JAN./12th/24 | MATERIAL   | WEIGHT | SCALE | REV |
| FOR INFORMATION ONLY<br>NOT FOR MANUFACTURING PURPOSES |       |              | UVFS   | 53.57g | 3:2   | A   |